



Docket No.: 006365 USA/MTCG/PCTRL/JW

PATENT/OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re: Application of

Yuri KOKOTOV et al.

Serial No. 10/712,273

Filed: November 14, 2003

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Group Art Unit: 2123

Examiner:

For: METHOD, SYSTEM AND MEDIUM FOR CONTROLLING MANUFACTURE  
PROCESS HAVING MULTIVARIATE INPUT PARAMETERS

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

Honorable Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Copies of any cited U.S. Patents and U.S. Patent Publications are not being submitted in accordance with 37 CFR 1.98(a)(2)(i).

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

In accordance with 37 C.F.R. § 1.97(g) and (h), the filing of this IDS should not be construed as a representation that a search had been made or that information cited is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56 (b), or that any cited document listed or attached is (or constitutes) prior art. Unless otherwise indicated, the date of

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publication indicated for an item is taken from the face of the item, and Applicant reserves the right to prove that the date of publication is in fact different.

No fee is believed to be required; however, the Commissioner is authorized to charge any deficiency in any fees pursuant to 37 CFR § 1.17 associated with this communication and to credit any excess payment to Deposit Account No. 08-0219.

Respectfully submitted,

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<b>INFORMATION DISCLOSURE</b> <b>CITATION IN AN APPLICATION</b> <b>(PTO-1449)</b>				ATTY. DOCKET NO. 006365 USA/ MTCG/PCTRL		SERIAL NO. 10/712,273	
				APPLICANT Yuri KOKOTOV et al.			
				FILING DATE November 14, 2003		GROUP	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
	Boning, Duane et al. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans.</i> October 1996. Vol. 19, No. 4. pp. 307-314.						
	Moyne, James et al. "A Run-to-Run Control Framework for VLSI Manufacturing." <i>Microelectronic Processing '93 Conference Proceedings.</i> September 1993.						
	Telfeyan, Roland et al. "Demonstration of a Process-Independent Run-to-Run Controller." <i>187<sup>th</sup> Meeting of the Electrochemical Society.</i> May 1995.						
	Moyne, James et al. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Adv. Semiconductor Manufacturing Conference.</i> August 15, 1995.						
	Moyne, James et al. "Adaptive Extensions to be a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology.</i> 1995.						
	Sachs, Emanuel et al. "Process Control System for VLSI Fabrication."						
	Chaudhry, Nauman et al. "Active Controller: Utilizing Active Databases for Implementing Multi-Step Control of Semiconductor Manufacturing." <i>University of Michigan.</i> pp. 1 – 24.						
	Chaudhry, Nauman et al. "Designing Databases with Fuzzy Data and Rules for Application to Discrete Control." <i>University of Michigan.</i> pp. 1 – 21.						
	Chaudhry, Nauman A. et al. "A Design Methodology for Databases with Uncertain Data." <i>University of Michigan.</i> pp. 1 – 14.						
	Khan, Kareemullah et al. "Run-to-Run Control of ITO Deposition Process." <i>University of Michigan.</i> pp. 1 – 6.						
	Moyne, James et al. "Yield Improvement @ Contact Through Run-to-Run Control."						
	Kim, Jiyoung et al. "Gradient and Radial Uniformity Control of a CMP Process Utilizing a Pre- and Post-Measurement Strategy." <i>University of Michigan.</i>						
EXAMINER				DATE CONSIDERED			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.